



Session Title:	[TuD2] Advanced Lithography II
Session Date:	November 12 (Tue.), 2024
Session Time:	15:00-16:30
Session Room:	Room D (Sidney Room, 2F, Paradise Hotel Busan)
Session Chair:	Prof. Sangsul Lee (POSTECH, Korea)

[TuD2-1] [Invited]

15:00-15:30

TEL's Challenge for High NA EUV

Kyounggho Jang, Chang-Sub Mun, Hyungi Kim, Sangwoo Lee, Youngseop Rah, Chang-gu Jung, Changwon Choi, Seongtae Oh, Jun Kim, Jay Lee, and Youngwoo Park (Tokyo Electron Korea Ltd., Korea)

[TuD2-2] [Invited]

15:30-16:00

High NA EUV Lithography: Prospects and Challenges

Seo-Min Kim (SK hynix Inc., Korea)

[TuD2-3] [Invited]

16:00-16:30

High NA EUV: What does it change for Design, OPC and Mask?

Youssef Drissi, Yasser Sherazi, Victor Blanco, Kenichi Miyaguchi, Werner Gillijns, and Ryan Ryoung Han Kim (imec, Belgium)